

Recent Achievements of the ATLAS Upgrade Planar Pixel Sensors R&D Project

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for the ATLAS PPS Collaboration

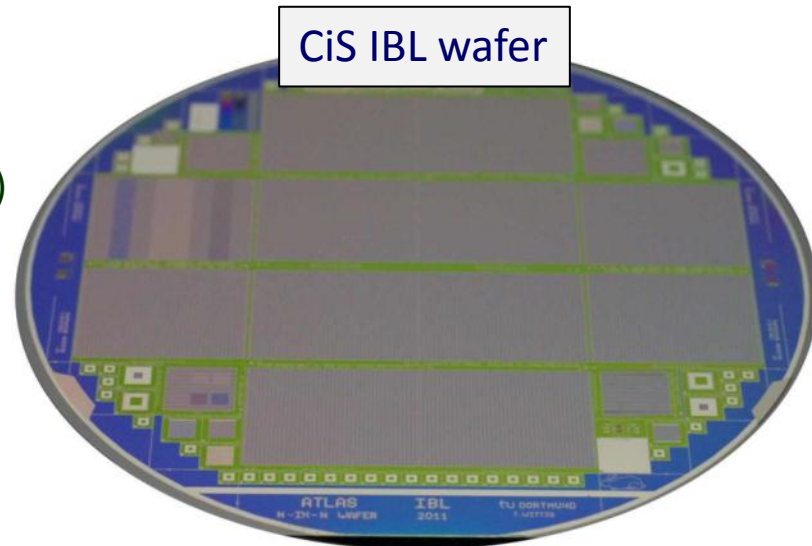
- Planar IBL Production
- Radiation Hardness
- Thin sensors
- Slim/Active edge
- HL-LHC Intermediate Layers
- Simulation
- Testbeams

Presenting the work of many people.
Sorry, if I mislabelled/-represented your plots/results/work.

IBL sensor production finished:

- 9 batches from CiS, 150 accepted wafers
 - ➔ 544 functional double-chip sensors (target was 448 DC) plus 409 single-chip sensors (R&D)
 - ➔ 160 tiles built into modules
 - ➔ 220 available with UBM

	batch 1	batch 2	batch 3	batch 4	batch 5	batch 6	batches 7-9	sum
received wafers	20	22	18	20	17	22	31	150
received DCS	80	88	72	80	68	88	124	600
good DCS	69	76	64	70	62	83	121	544
yield	86.3%	86.4%	88.9%	87.5%	91.2%	94.3%	97.6%	90.6%

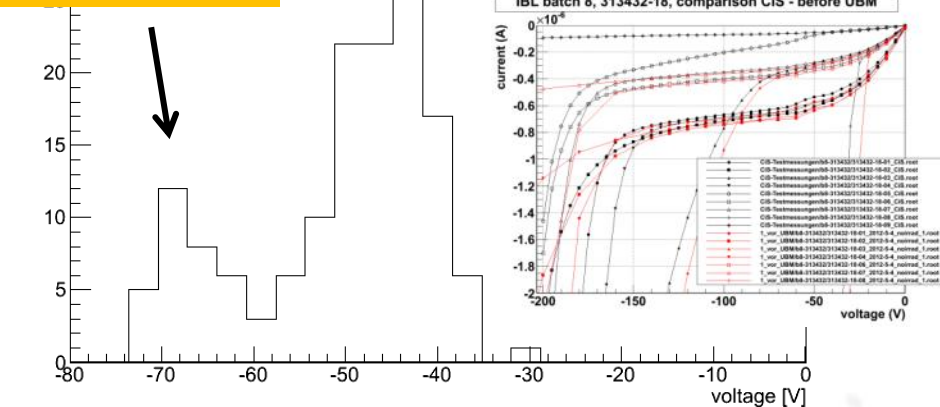
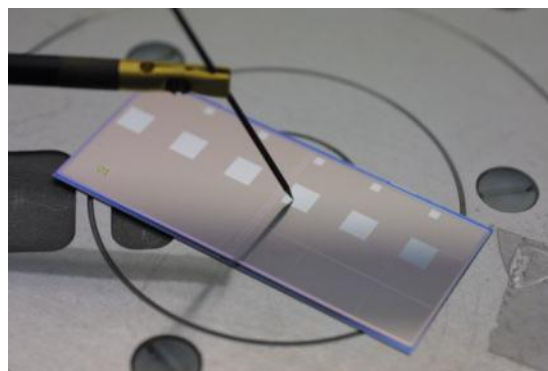
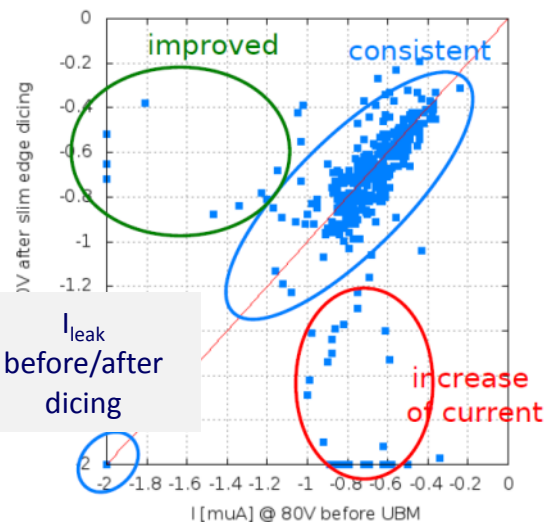


$V_{dep} = 46 \pm 6$ V
for first batches

IBL production, batch 1-9, depletion voltage, CiS measurements, accepted wafers

increased V_{dep}
for last batches

voltage distribution
Entries 150
Mean -50.49
RMS 10.04

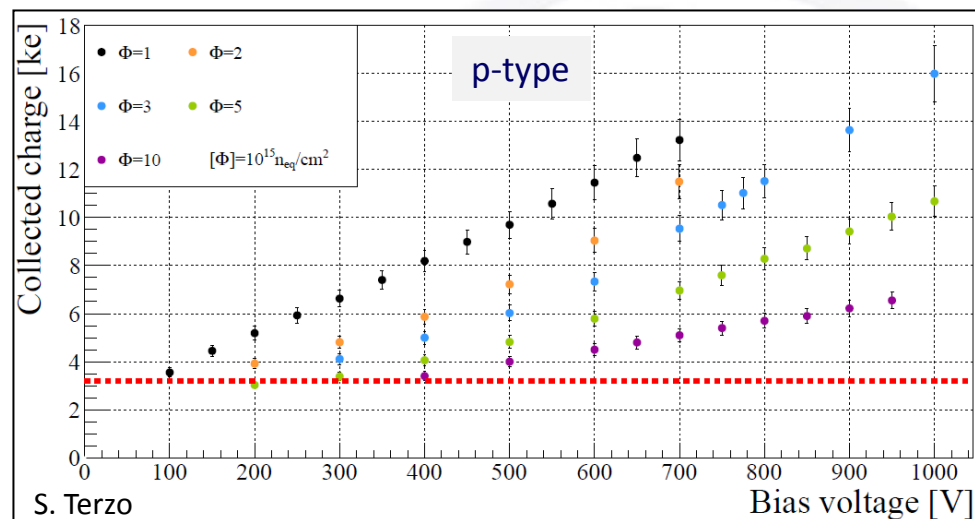
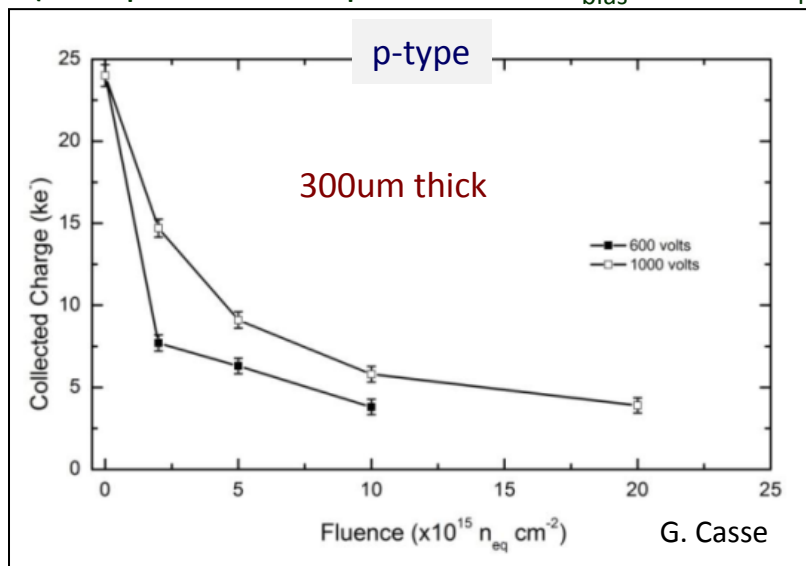
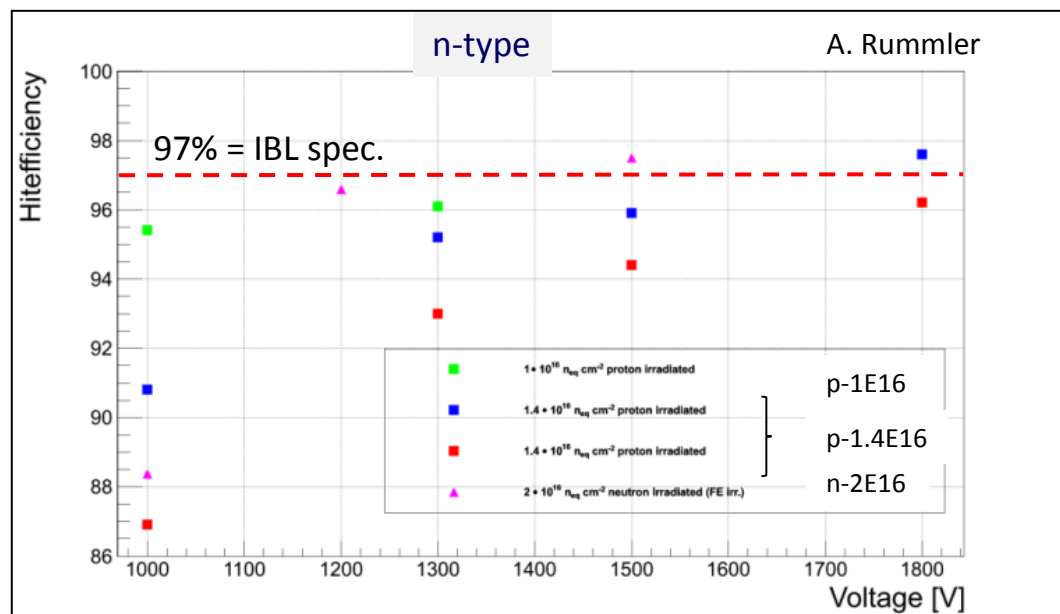


Plots stolen from T. Wittig

Radiation hardness of planar n- and p-bulk sensors

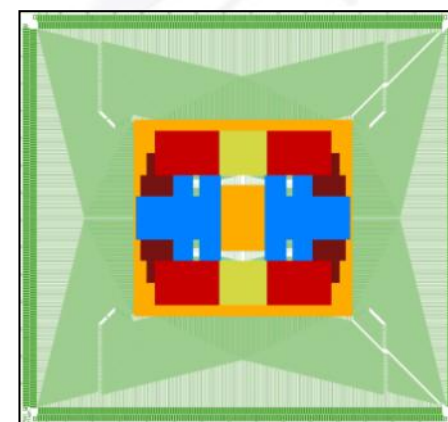
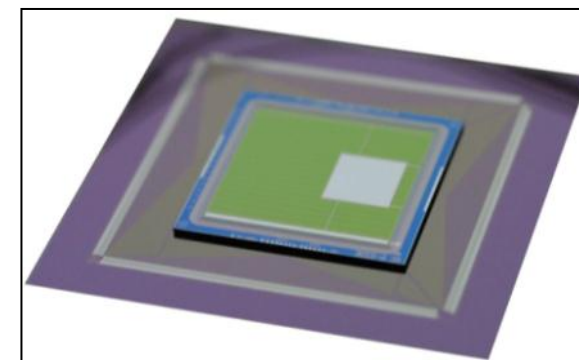
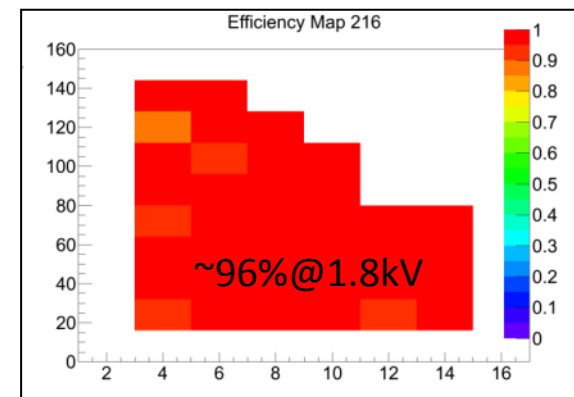
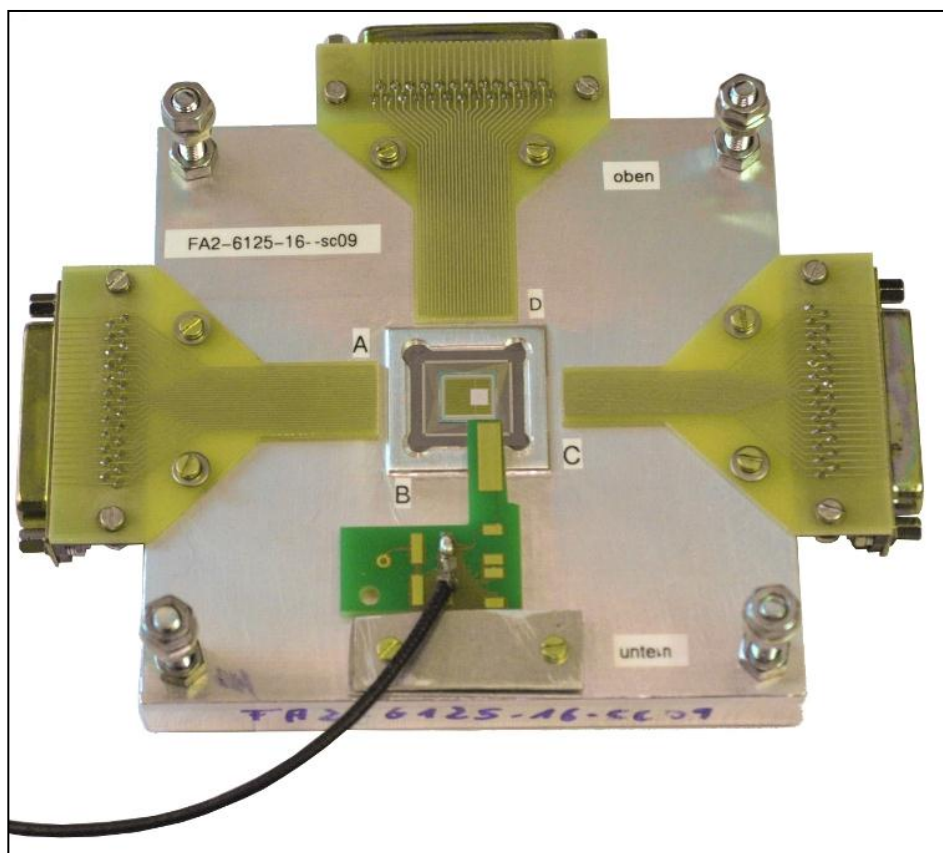
→ Irradiations reaching the $1\text{-}2\text{E}16\text{ n}_{\text{eq}}/\text{cm}^2$ region:
(here: compare 'thick' sensors, $O(300\mu\text{m})$)

- n-type sensors shown to work at $2\text{E}16\text{ n}_{\text{eq}}/\text{cm}^2$
(old ATLAS production, $V_{\text{bias}} \geq 1\text{kV}$, $4\text{ke} < Q_{\text{mip}} < 8\text{ke}$)
- p-type sensors shown to work at $1\text{E}16\text{ n}_{\text{eq}}/\text{cm}^2$
(MPP CiS production, $V_{\text{bias}} \leq 1\text{kV}$, $Q_{\text{mip}} \leq 6\text{ke}$)
- p-type strip sensors studied up to $2\text{E}16\text{ n}_{\text{eq}}/\text{cm}^2$
(Liverpool Micron production, $V_{\text{bias}} \leq 1\text{kV}$, $Q_{\text{mip}} < 5\text{ke}$)



Try to separate FE- and sensor effects:

- 'low temperature' In bumping (FE-I3)
- new fan-out structure to connect pixels to external readout (e.g. ALIBAVA or commercial CSA)

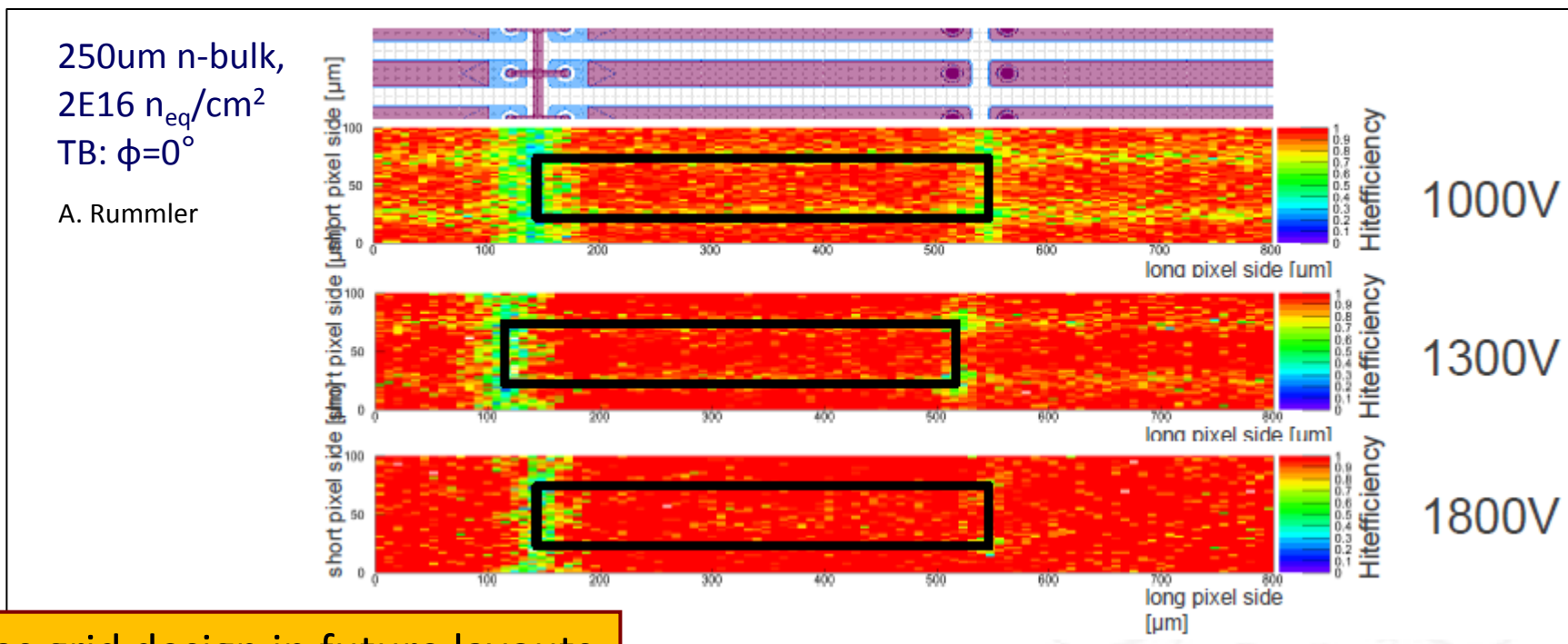
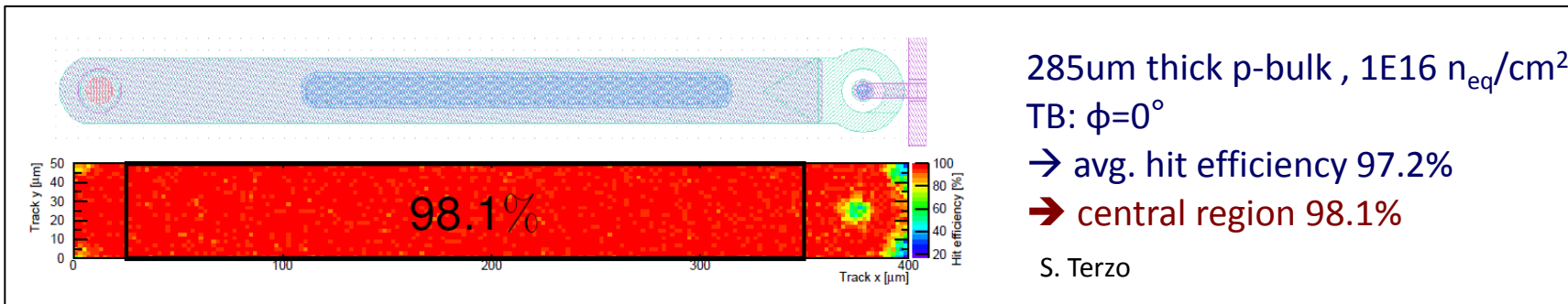


Plots from Dortmund (A. Rummler and T. Plümer)

One of the earliest testbeam results:

Main loss of hit efficiency at the bias dot and the trail leading to it ('bias rail').

(True for both n- and p-bulk sensors)

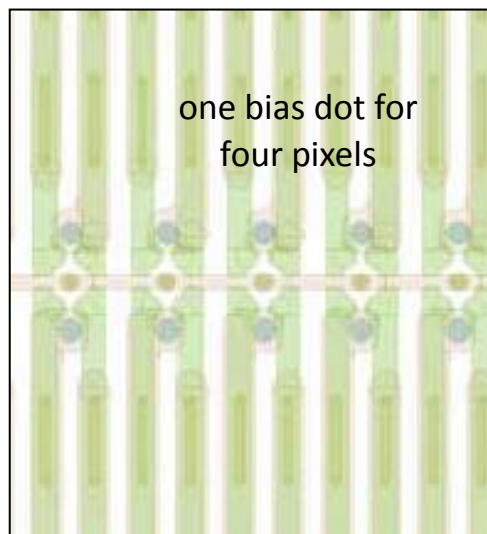
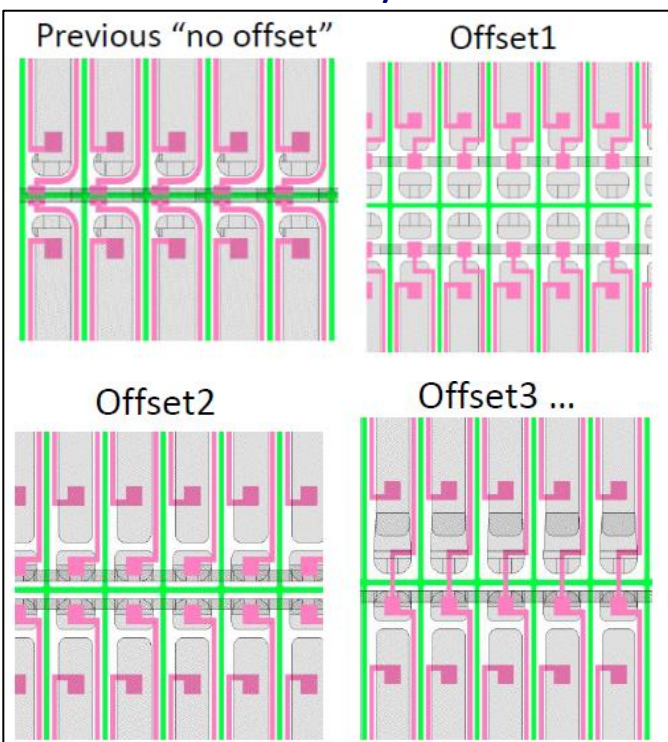


After many discussions and simulations (more from Nobu) several new bias grid/rail layouts under investigation.

Sensor productions ongoing:

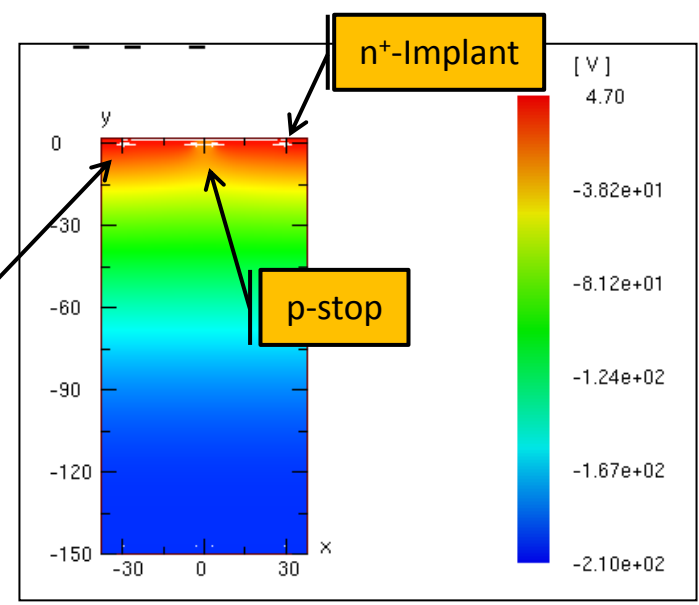
- CiS n-bulk
- CiS p-bulk
- HPK p-bulk

KEK layout

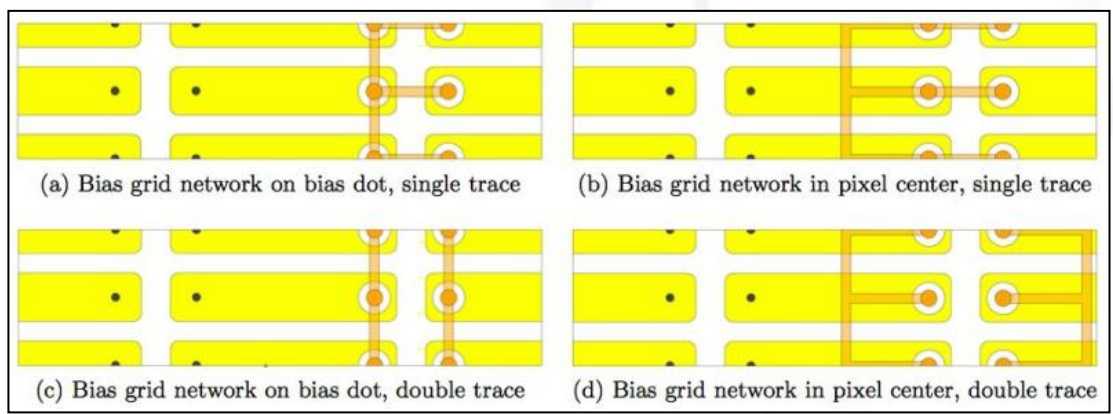


n⁺-Implant

p-stop

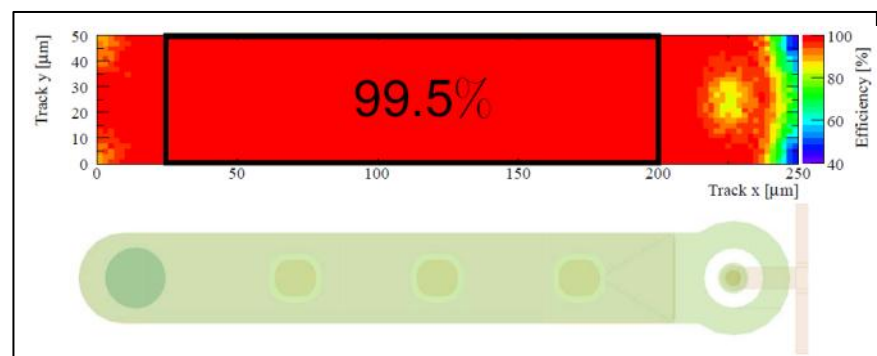
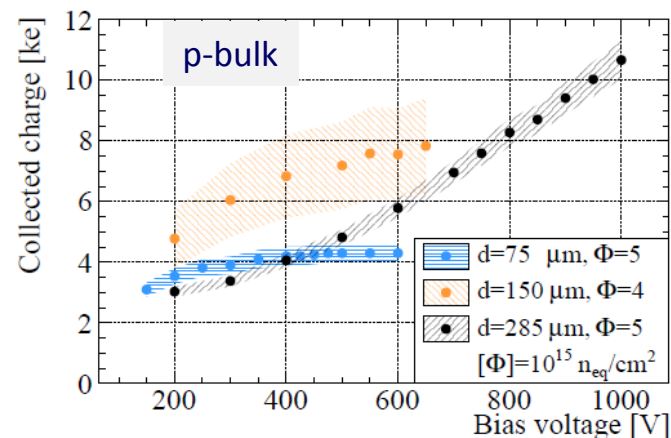
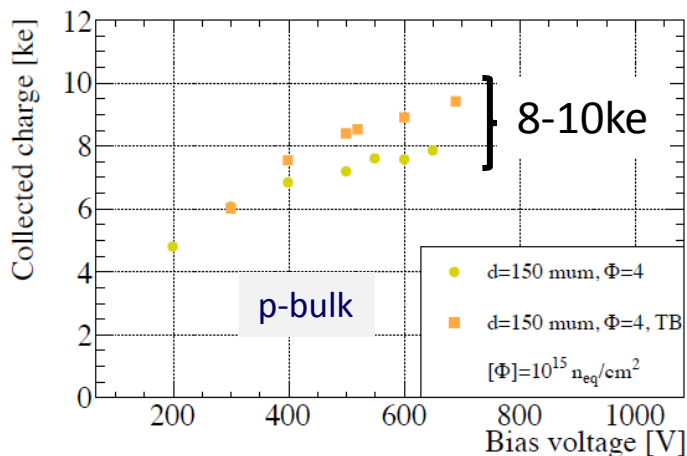


Dortmund layout



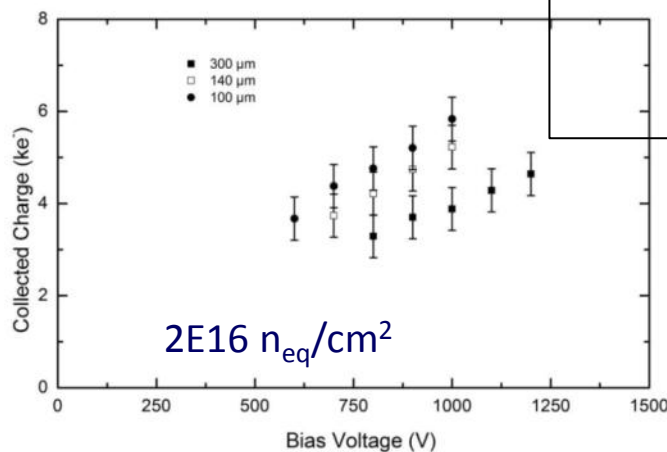
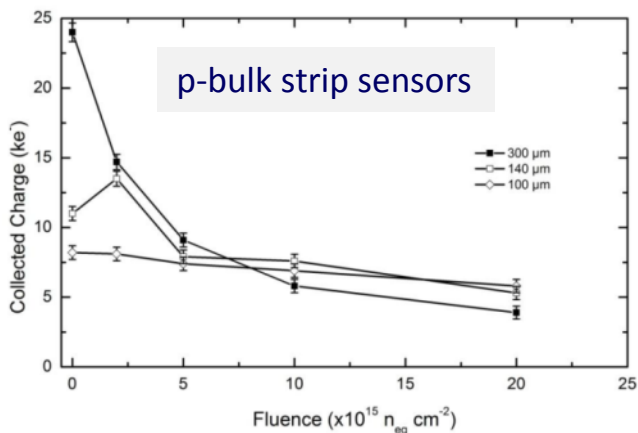
Thin sensors

- perform as expected (similar to thick ones) before irradiation
 - offer substantial advantages above fluences of $5E15 \text{ n}_{\text{eq}}/\text{cm}^2$
 - studying thickness between 150 μm and 75 μm
 - samples irradiated up to $2E16 \text{ n}_{\text{eq}}/\text{cm}^2$
- ➔ much more detail in the next few talks



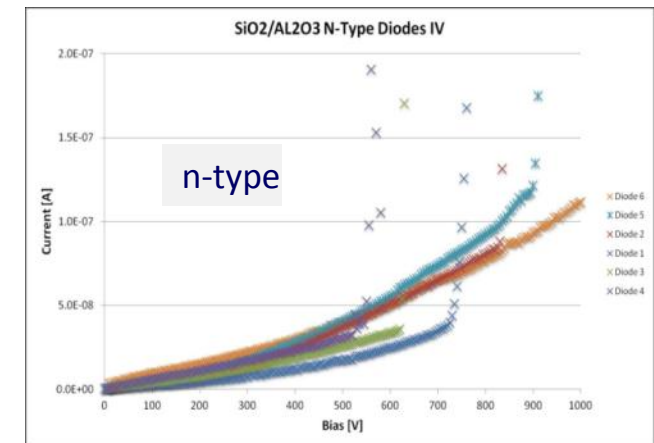
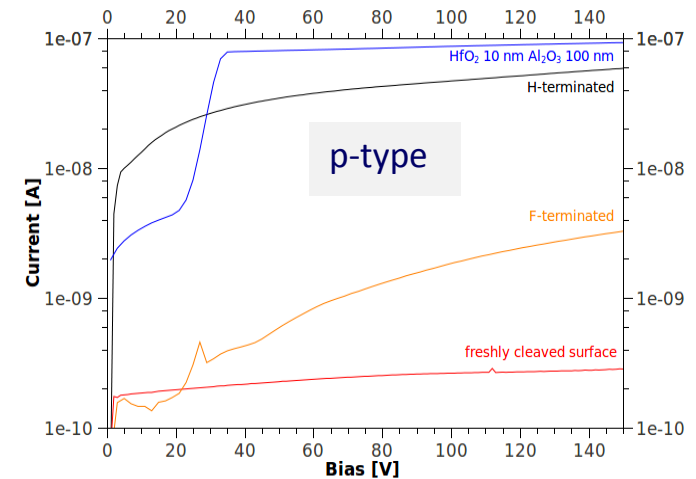
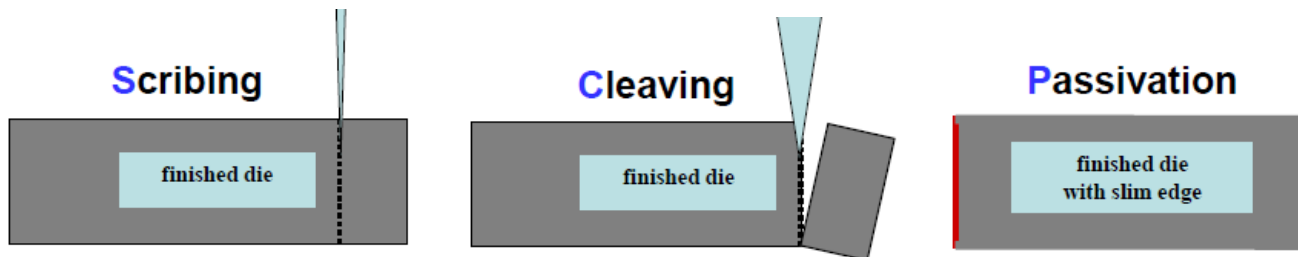
p-bulk 150 μm , p- $4E15 \text{ n}_{\text{eq}}/\text{cm}^2$,
V_{bias}=690V, TB $\phi=0^\circ$,
avg. hit efficiency 97.7%

Plots stolen from S. Terzo and G. Casse



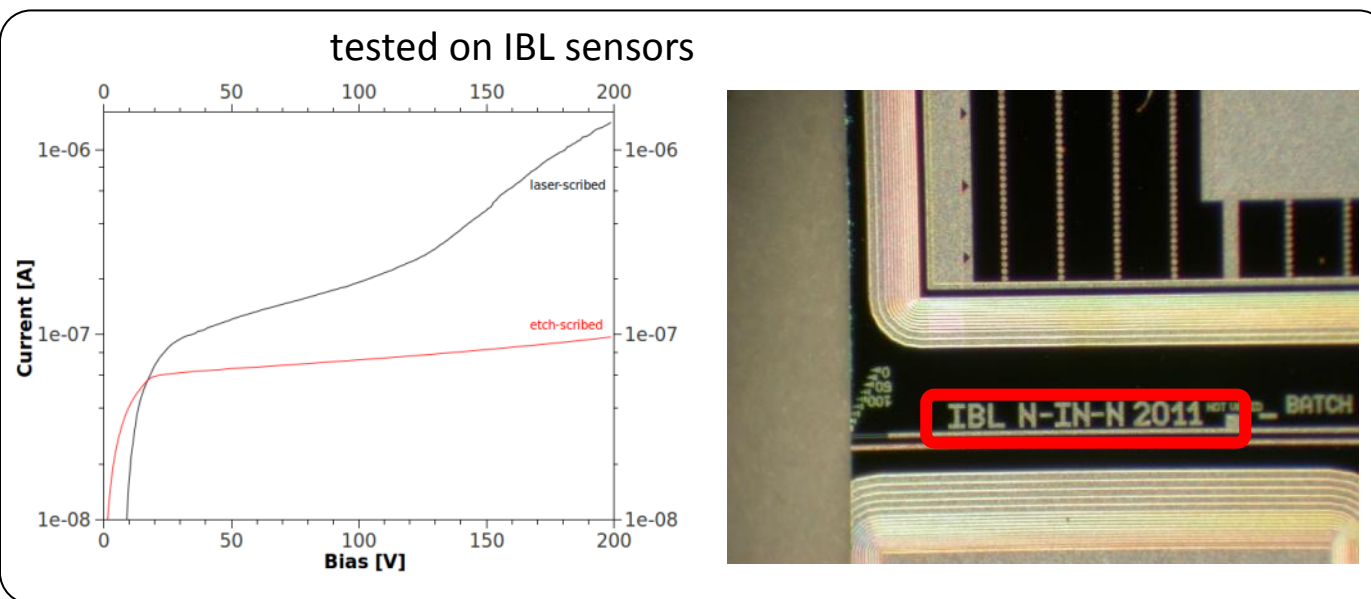
Scribe-Cleave-Passivate technology

- reduce edge width significantly
- treatment is post-processing and low-temperature
- different scribe-techniques, DRIE looks most promising
- trying to industrialize cleaving
- surface termination non-trivial



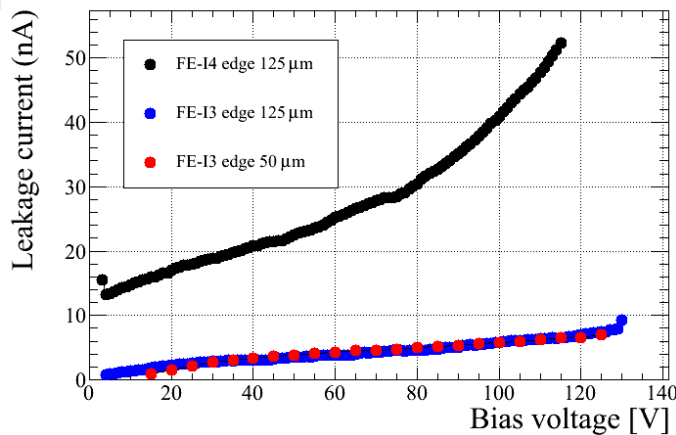
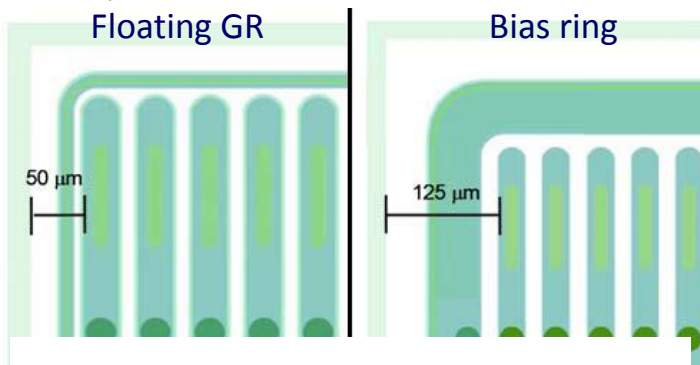
Plots stolen from V. Fadeyev

More details from H. Sadrozinski

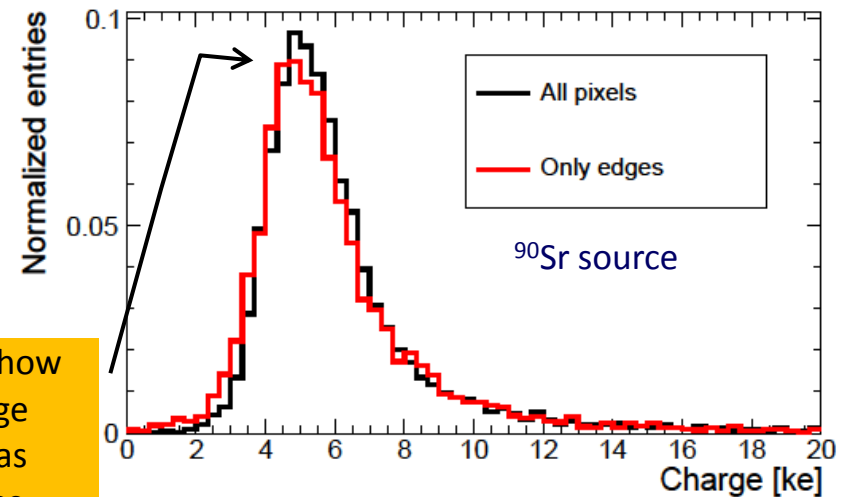
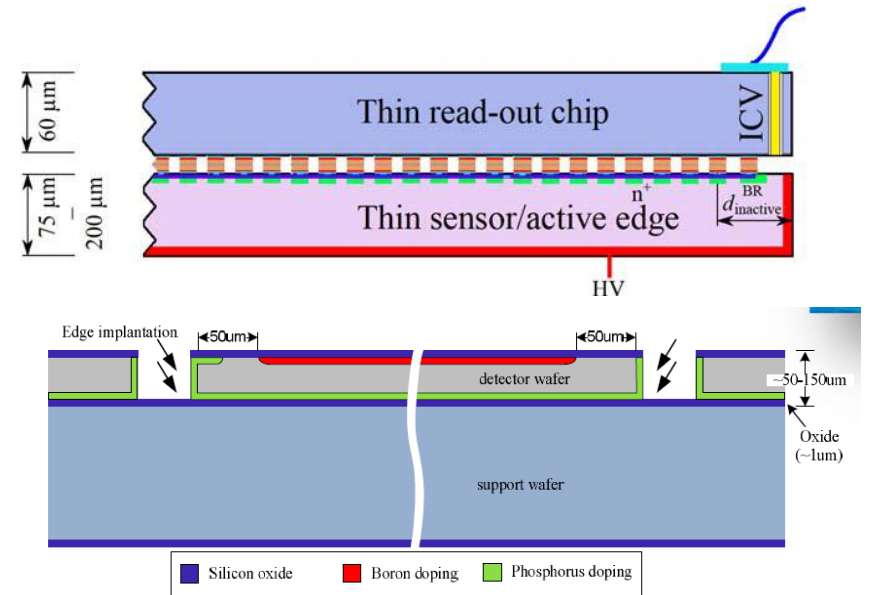


Active Edge sensors

- MPP/VTT:
 - towards 4-side buttable sensors using TSV
 - MPW run at VTT: different edge designs, 100um and 200um thick, p-spray
 - flip-chip done at VTT
 - 100um samples: $V_{dep} \sim 7-10V$, $V_{break} \sim 120V$, $Q_{mip} \sim 6 \pm 1ke$

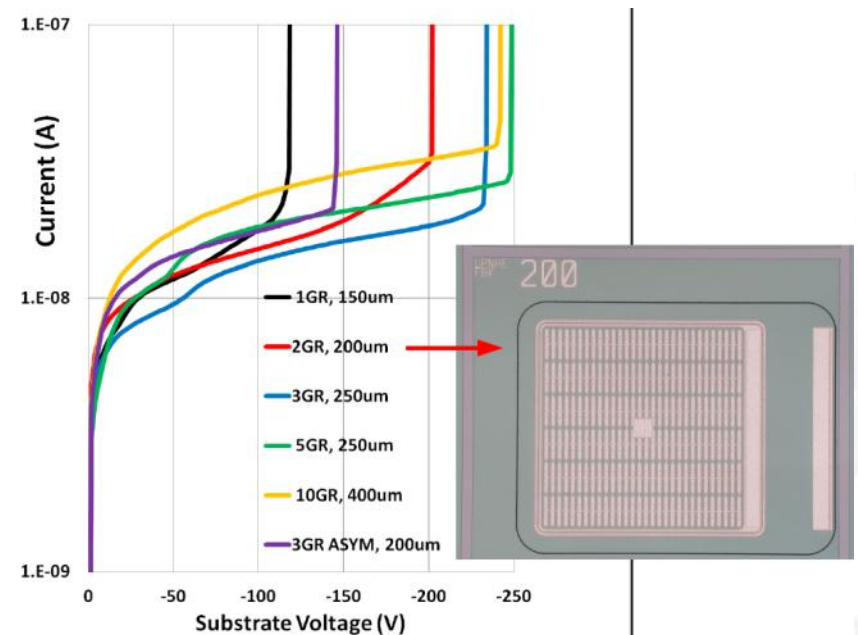
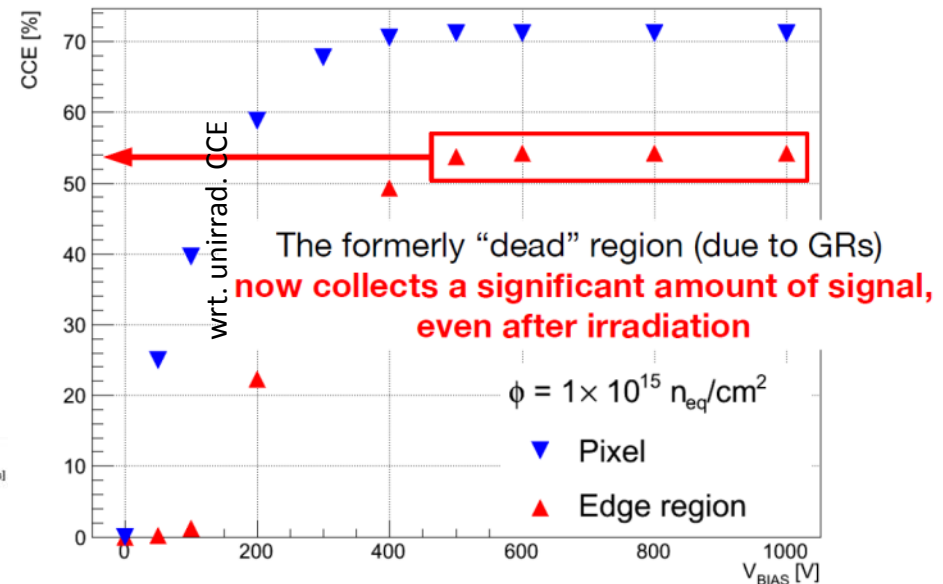
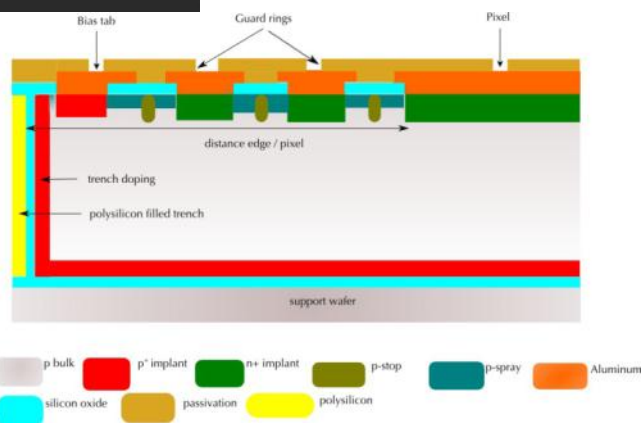
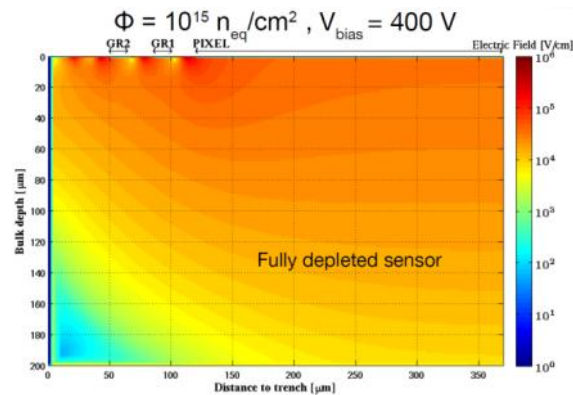
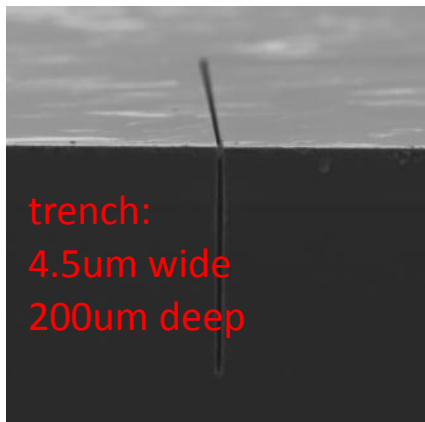


edge pixels show same charge collection as center ones



Plots stolen from A. Macchiolo

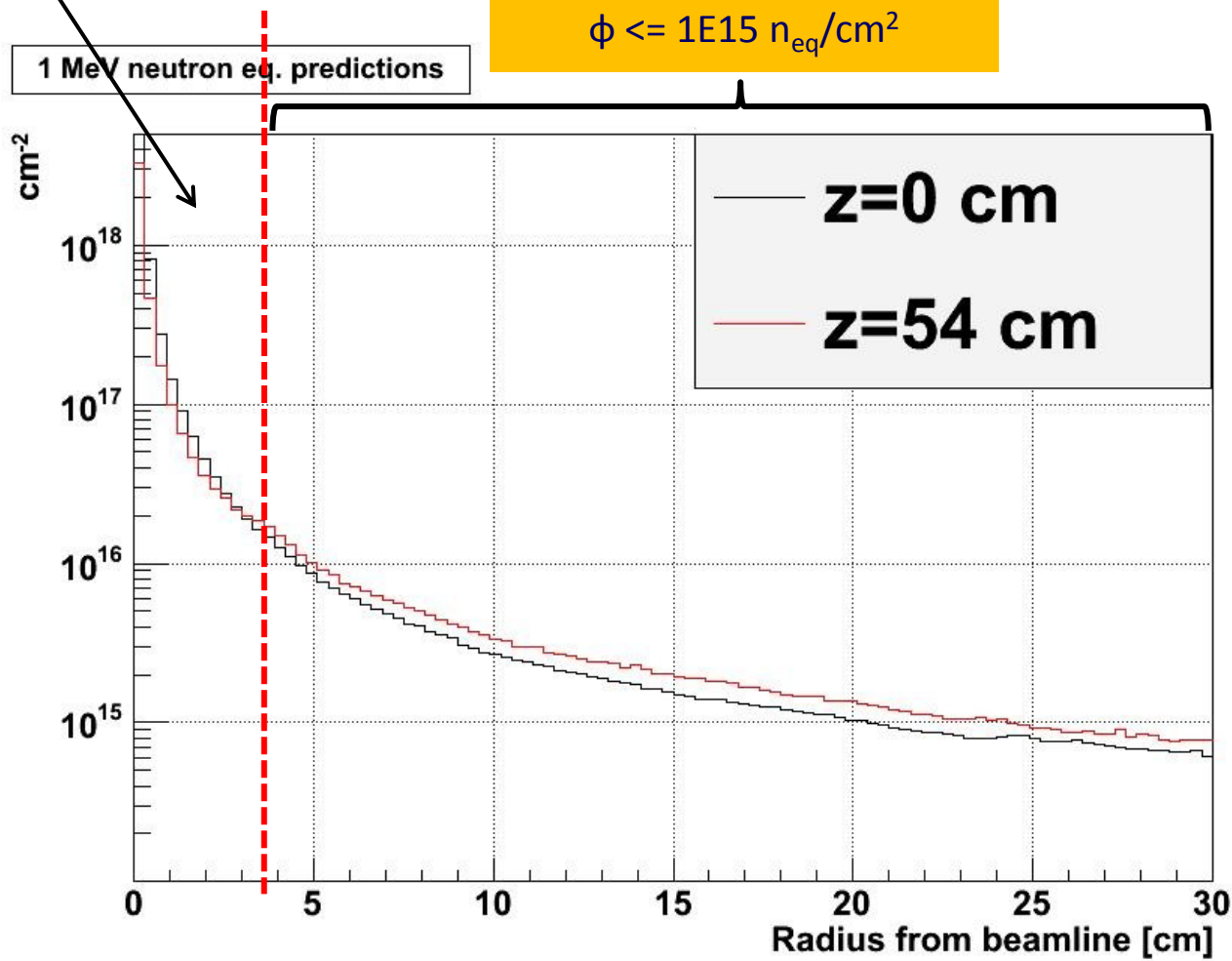
- LPNHE/FBK:
 - DRIE trench etching, sidewall doped by diffusion
 - different GR and edge designs
 - a lot of simulation done (Silvaco 2D TCAD)
 - first sensors in hand
 - ➔ first measurements look promising



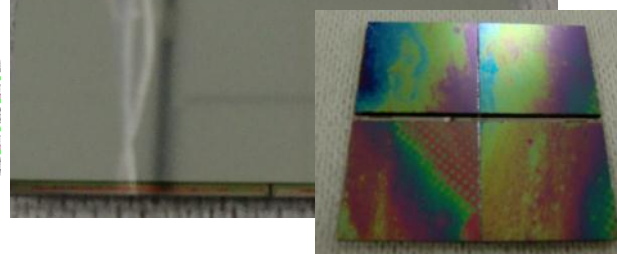
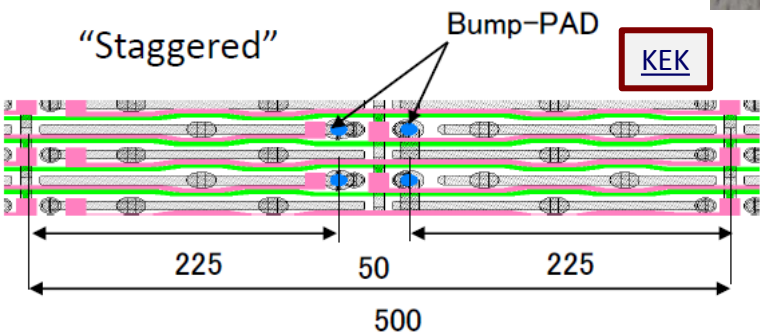
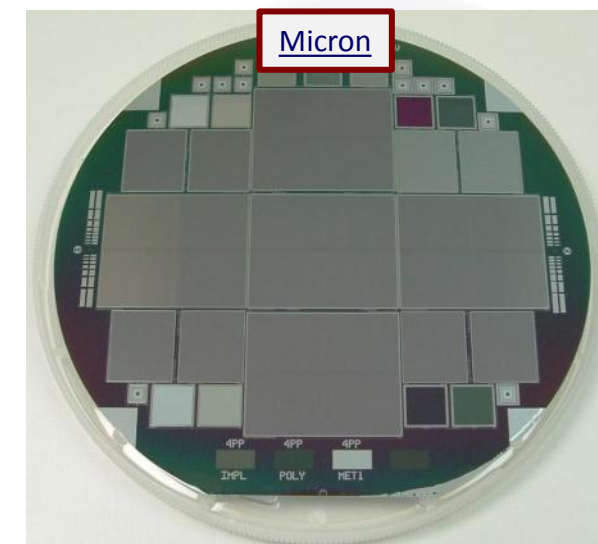
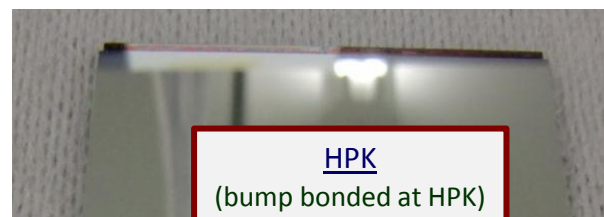
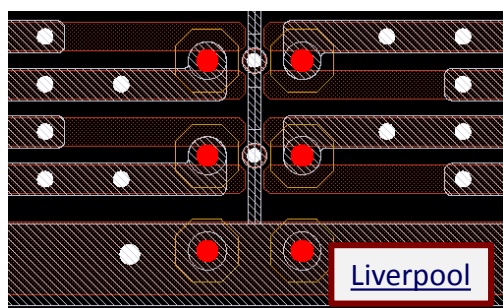
Plots stolen from M. Bomben

inner layer:
 $\phi = 2E16 \text{ n}_{\text{eq}}/\text{cm}^2$

intermediate layers:
 $\phi \leq 1E15 \text{ n}_{\text{eq}}/\text{cm}^2$

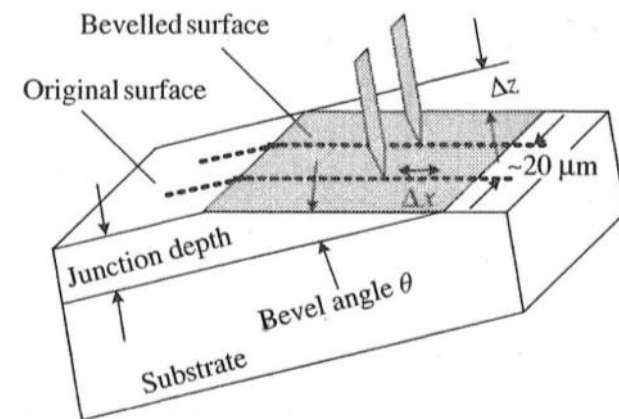
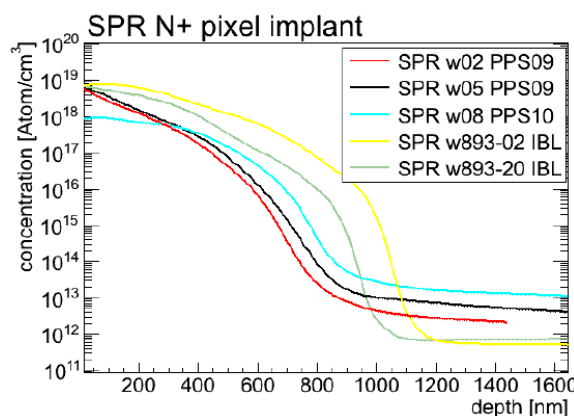
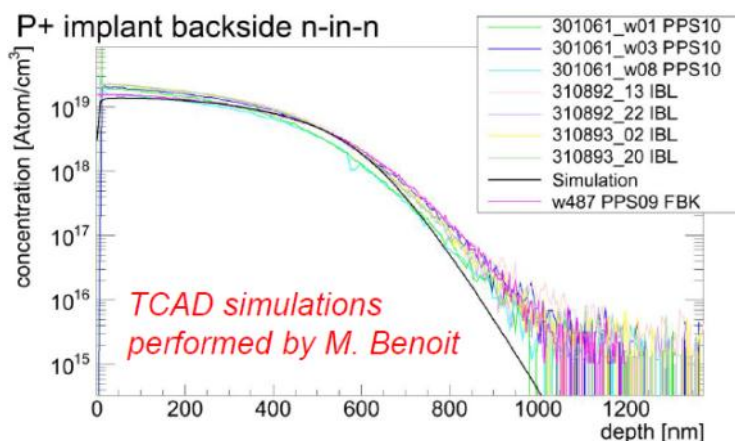
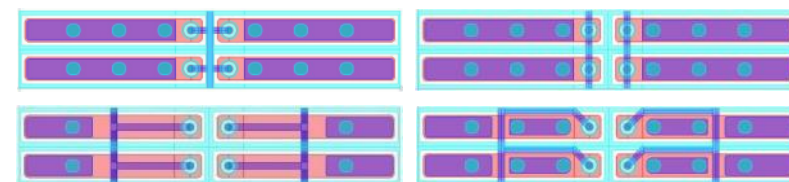
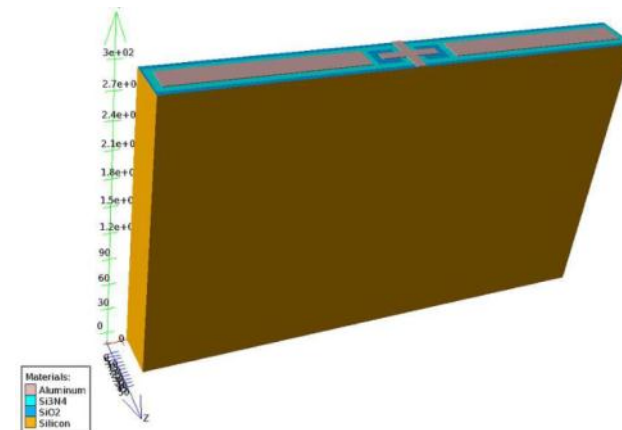


1. MCz seems promising in this mixed radiation field
 - irradiate, test , compare to DOFZ material
2. main topic: cost reduction
 - ➔ 2x2 chip sensors to reduce handling cost
 - most institutes producing ‘pseudo’-quad modules using two existing 1x2 chip tiles
 - dedicated sensor productions planned or under way at CiS (n- and p-type), Micron, HPK
 - improving resolution in $R\phi$ by reducing pixel pitch
 - ➔ $25 \times 500 \text{ } \mu\text{m}^2$ (compatible w/ FE-I4 bump pattern)
 - (also working on PCB and R/O system (KEK))



TCAD simulation activities

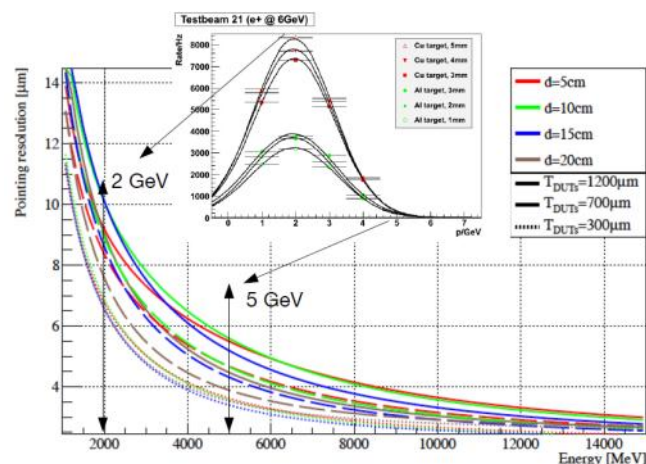
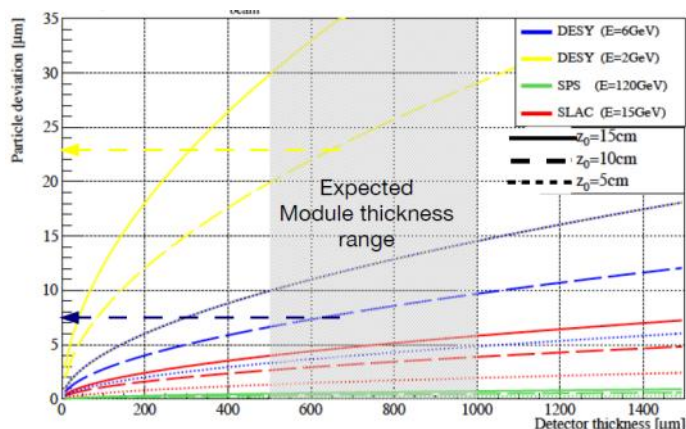
- trying to model 3D electric field distribution for two pixels
- model different bias grid designs
- problem: restricted number of mesh points (esp. on electrodes)
 - ➔ numerical calculation doesn't converge for n-in-n and n-in-p samples
- improving simulation by accurate modeling of doping concentration
 - ➔ dopant depth profiling by
 - Secondary Ion Mass Spectroscopy (SIMS): total dopant density profile
 - Spreading Resistance Profiling (SRP) or Scanning Spreading Resistance Measurement: carrier density profile



Plots stolen from V. Linhard and N. Dinu

Testbeams in 2012 and beyond

- ~62 days in 4 periods at DESY and CERN
- sometimes running on two beamlines in parallel
- took nearly 900 GB of data
- hundreds of configurations of different samples tested
- ‘Too many testbeams this year.’ M. Bomben
 - same people running TB and analyzing results
 - very busy getting analysis done in time
 - still produced the very nice results you have been seeing in this talk and many more!
- no beam at CERN in 2013, restart 2014 not clear yet
 - ➔ many requests submitted to DESY (4-6 GeV electrons, very busy)
 - ➔ beam time requested at SLAC (15 GeV electrons...)



Very good and fruitful collaboration between ATLAS Pixel Upgrade R&D groups

- common hardware
- common beam requests
- ➔ simplified TB organization

Plots and photo stolen from M. Bomben

Thank you for your attention.



Seabas system

